



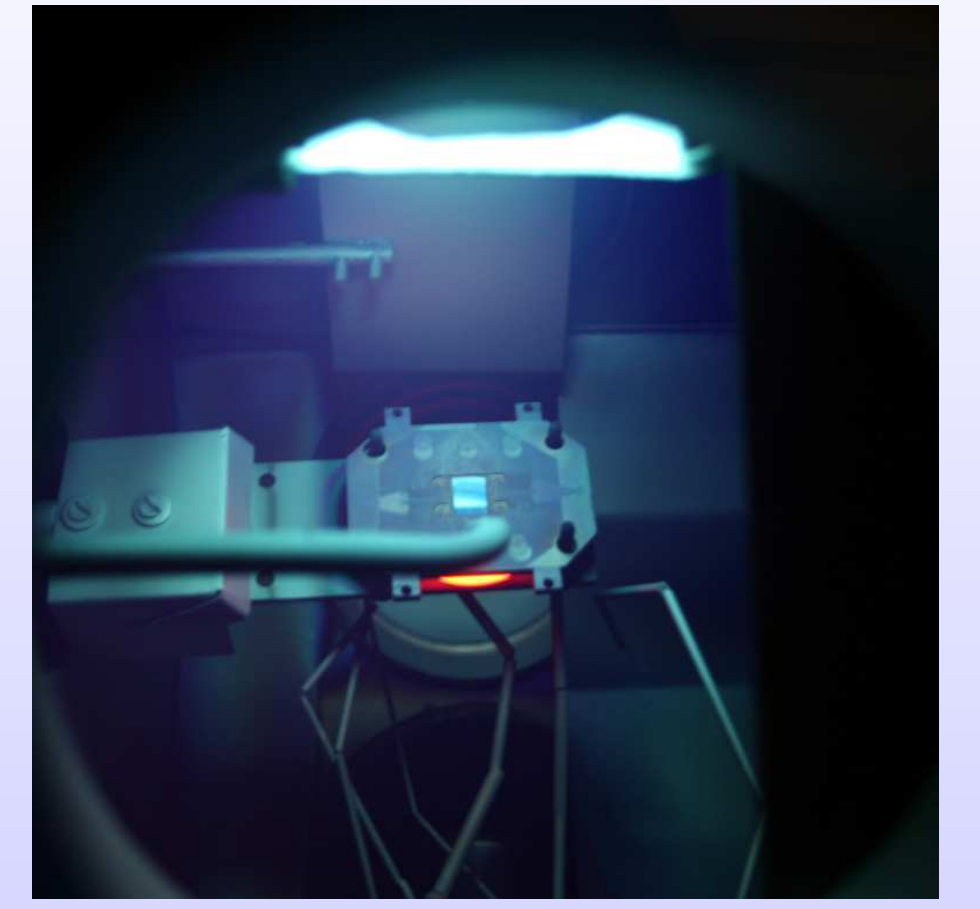
Low pressure hydrogen discharges diluted with argon

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Introduction

- A global (volume averaged) model is applied to study a low pressure (1 - 100 mTorr) high density H₂/Ar discharge in the steady state.
- Based on a previous model of the Cl₂/Ar discharge (Thorsteinsson and Gudmundsson, 2010)

The global (volume averaged) model

- In addition to electrons the discharge consists of ground state atoms (H, Ar), molecules (H₂), positive ions (H⁺, H₂⁺, H₃⁺, Ar⁺, ArH⁺) negative ions (H⁻), vibrationally excited molecules (H₂($v = 1 - 14$)), electronically excited atoms (Ar(4p)), metastables (Ar^m (1s₅ and 1s₃)) and radiatively coupled states (Ar^r (1s₄ and 1s₂)).
- Electrons are assumed to have a Maxwellian energy distribution in the range 1 - 10 V.
- The collisional energy loss per electron-ion pair created is defined as

$$\mathcal{E}_c = \mathcal{E}_{iz} + \sum_i \mathcal{E}_{ex,i} \frac{k_{ex,i}}{k_{iz}} + \frac{k_{el} 3m_e T_e}{k_{iz} m_i} \quad (1)$$

where \mathcal{E}_{iz} is the ionization energy, $\mathcal{E}_{ex,i}$ is the threshold energy and $k_{ex,i}$ is the rate coefficient for the i -th excitation process and k_{iz} is the ionization rate coefficient for single step ionization.

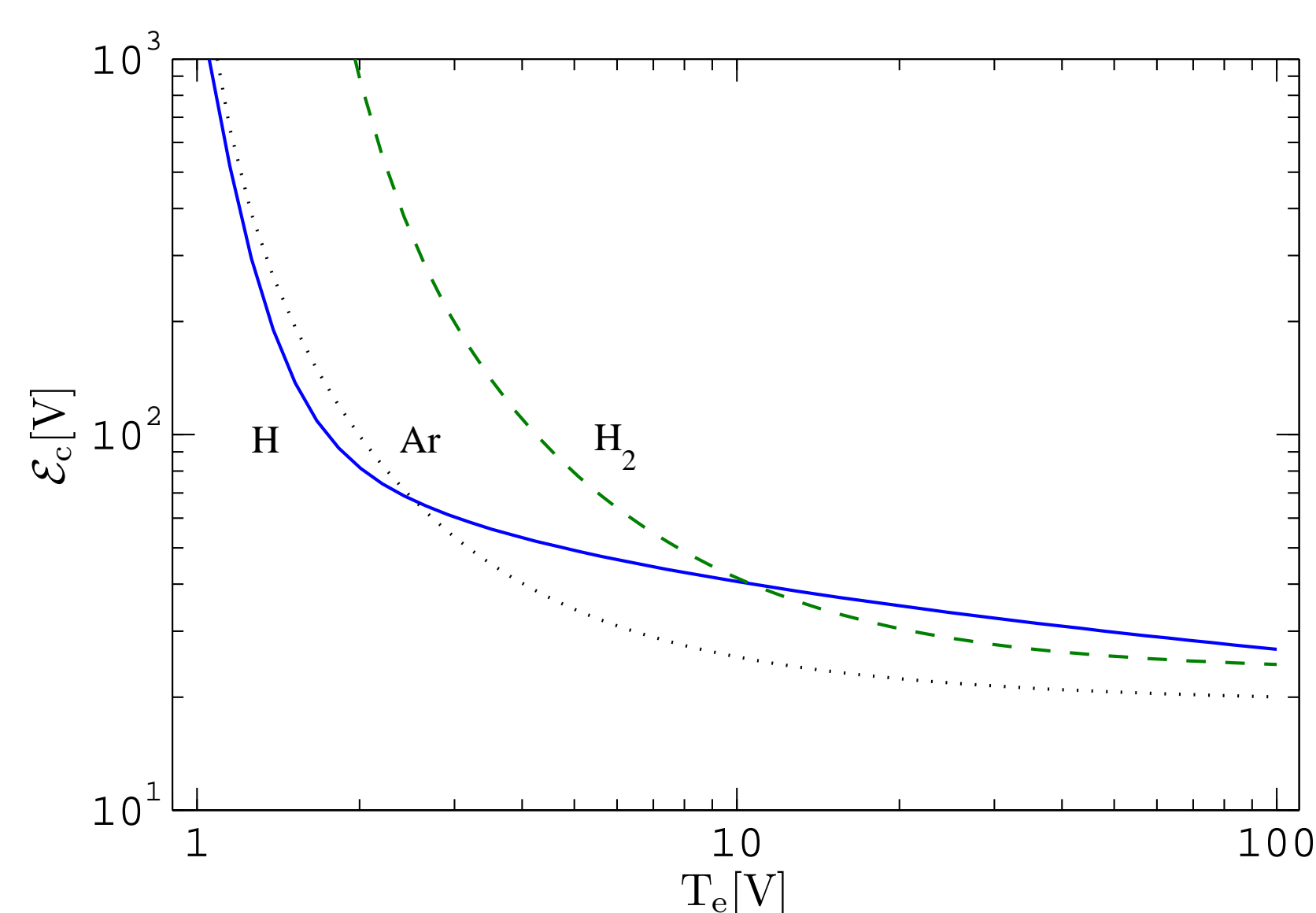


Figure 1: The calculated collisional energy loss \mathcal{E}_c per electron-ion pair created as a function of the electron temperature T_e for atomic and molecular hydrogen and the argon atom.

Results and discussion

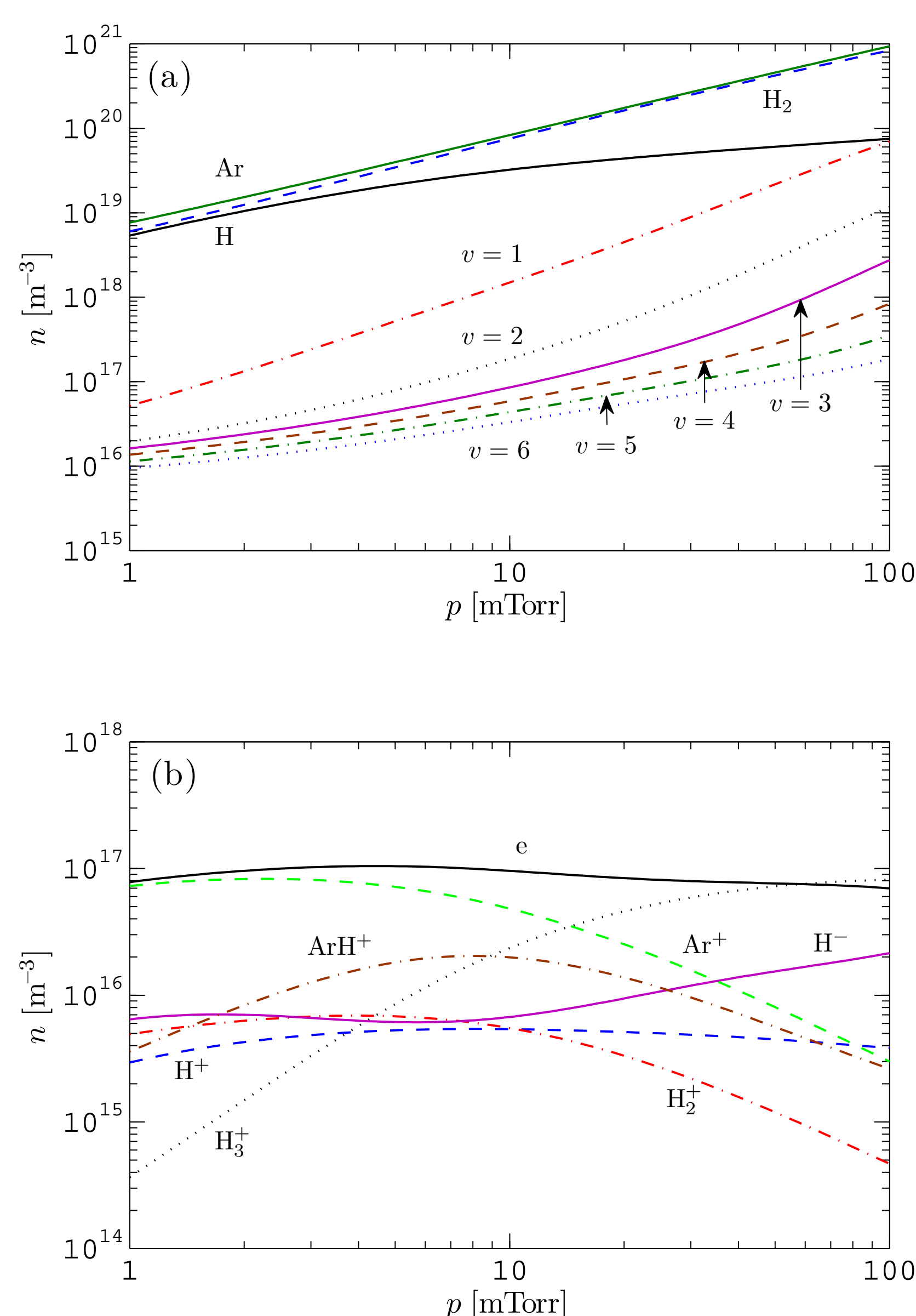


Figure 2: The (a) neutral particle densities and (b) the charged particle densities versus pressure at $R = 15.24$ cm, $L = 7.62$ cm, $Q = 50$ sccm, $P_{abs} = 600$ W, $T_g = 500$ K and 50% Ar dilution.

- The surface recombination coefficient for atomic hydrogen is assumed to be 0.023 (Curley et al., 2010) and the gas temperature is assumed to be $T_g = 500$ K.
- The atomic and molecular hydrogen densities are similar at 1 mTorr, but at 100 mTorr the atomic density is an order of magnitude lower.
- The $[H_2(v > 0)]/[H_2(v = 0)]$ ratio increases from 0.026 to 0.1 when the pressure is increased from 1 to 100 mTorr.
- The density of H⁻ is relatively small over most of the pressure range of interest but increases with increasing discharge pressure.
- Ar⁺ is the dominant positive ion in the discharge for pressures below 14 mTorr, for higher pressure H₃⁺ becomes the dominant positive ion.
- For very low pressures ($p < 2$ mTorr) there is a significantly higher density of H₂⁺ and H⁺ ions than the H₃⁺ ion. The density of H₃⁺ ions increases with increased pressure.

The density of ArH⁺ increases with pressure at first, peaking at roughly 8 mTorr but then it decreases again with increasing pressure.

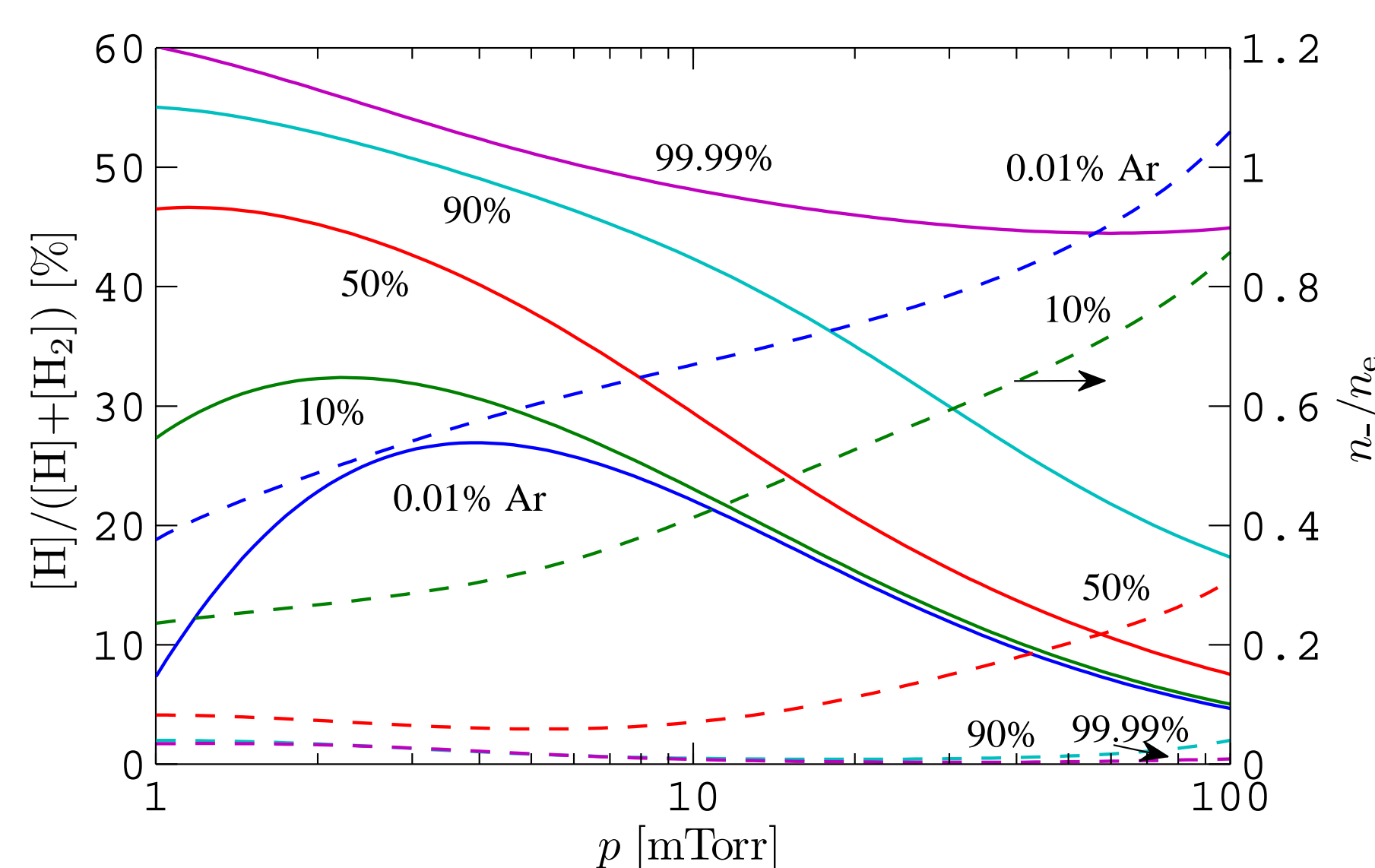


Figure 3: The dissociation fraction (solid lines) and electronegativity (dashed lines) versus pressure at $R = 15.24$ cm, $L = 7.62$ cm, $Q = 50$ sccm, $T_g = 500$ K and $P_{abs} = 600$ W..

- The dissociation fraction increases as the argon content increases.
- The electronegativity is low and decreases with increased argon content but increases with increased discharge pressure. It is at a maximum of 1.06 in a pure hydrogen discharge at 100 mTorr.
- It is well known that the dissociative attachment of hydrogen molecules is important in creating negative ions, in particular from the higher vibrational levels of the H₂ molecule.

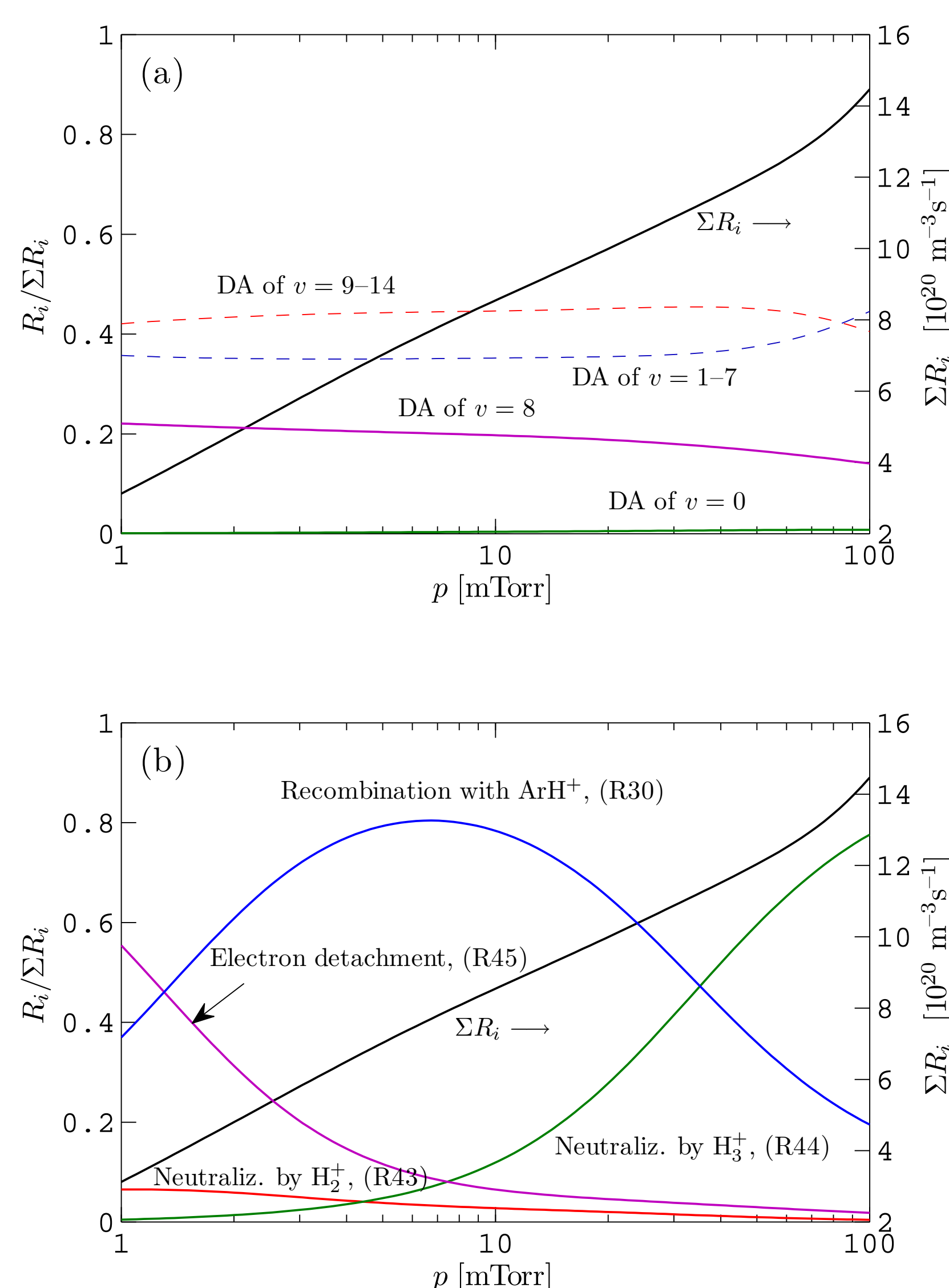


Figure 4: The absolute and relative reaction rates for (a) creation and (b) loss of H⁻ versus pressure at $R = 15.24$ cm, $L = 7.62$ cm, $Q = 50$ sccm, $T_g = 500$ K, $P_{abs} = 600$ W and 50% argon dilution.

- The cross section for dissociative attachment increases significantly when the molecule is vibrationally excited and the threshold decreases.
- Dissociative attachment of the $v=8$ vibrationally excited molecule is generally the most dominant individual contributor to the creation of H⁻ with 22% contribution at 1 mTorr.

- Dissociative attachment of H₂($v = 7$) and H₂($v = 9$) are also effective, contributing around 18% and 14%, respectively.
- The ion-ion recombination reaction



dominates the loss of H⁻ in the pressure range 1–36 mTorr, reaching 80% contribution at roughly 7 mTorr.

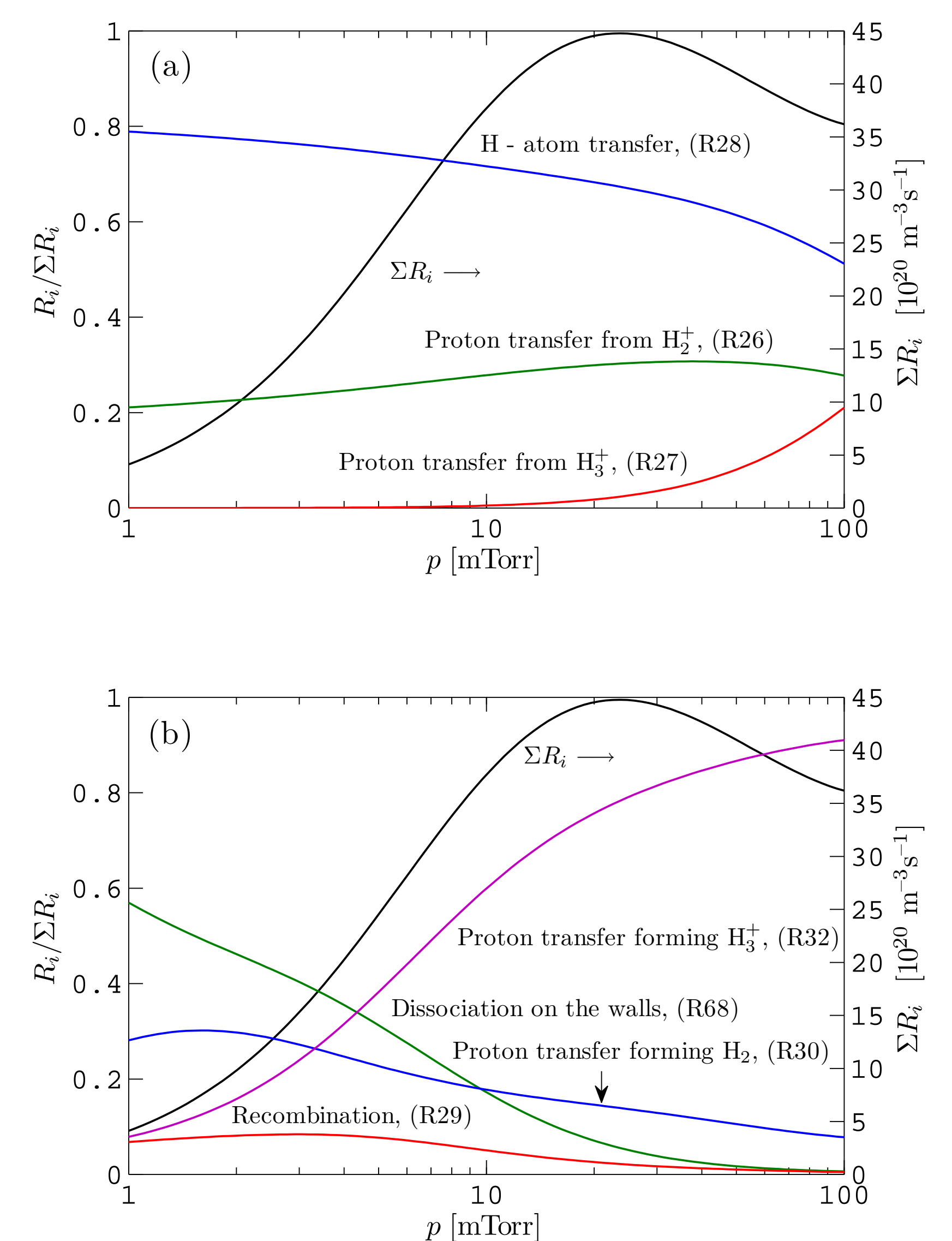


Figure 5: The absolute and relative reaction rates for (a) creation and (b) loss of ArH⁺ versus pressure at $R = 15.24$ cm, $L = 7.62$ cm, $Q = 50$ sccm, $T_g = 500$ K, $P_{abs} = 600$ W and 50% argon dilution.

- The atom transfer reaction



is most effective in the creation of ArH⁺ at all pressures, having almost 80% contribution at best at 1 mTorr.

- Dissociation on the walls and the proton transfer reaction



are the main contributors to the loss of ArH⁺.

Conclusions

- The effects of dissociative attachment on the creation of the negative ion H⁻ resulting from vibrationally excited states were explored, showing that dissociative attachment from the $v = \{7-9\}$ states contributes the most to the creation of H⁻ or about 50%.
- The contribution of the electron impact singlet excitation followed by a radiative decay to a vibrationally excited state is the most significant in the creation of the H⁻ ion and the role of the direct electron impact vibrational excitation is negligible in comparison.
- The density of the ArH⁺ is large, in particular in the pressure range 2–30 mTorr, and it plays a crucial role in the destruction of the H⁻ ion in this pressure range.

Acknowledgments

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References

- Curley, G. A., L. Gatilova, S. Guilet, S. Bouchoule, G. S. Gogna, N. Sirse, S. Karkari, and J. P. Booth (2010). Surface loss rates of H and Cl radicals in an inductively coupled plasma etcher derived from time-resolved electron density and optical emission measurements. *Journal of Vacuum Science and Technology A* 28(2), 360–373.
- Thorsteinsson, E. G. and J. T. Gudmundsson (2010). A global (volume averaged) model of a Cl₂/Ar discharge. I. Continuous power. *Journal of Physics D: Applied Physics* 43(11), 115201.